

# Atomistic Mechanisms of Orientation and Temperature Dependence in Gold-Catalyzed Silicon Growth

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Gold-catalyzed vapor-liquid-solid (VLS) growth is widely used in the synthesis of silicon-based low-dimensional nano-structures. However, growth anomalies are often observed [1, 2], whose formation is believed to highly depend on the growth orientation and temperature, but a complete understanding has not been achieved yet. In this talk, we present a systematic study on the orientation and temperature dependences in the VLS process [3], by means of long molecular dynamics (MD) simulations up to 100 ns using an MEAM potential that well reproduces the binary phase diagram [4]. The Si growth velocities are extracted from the simulations under various conditions for  $\langle 110 \rangle$  and  $\langle 111 \rangle$  orientations respectively. Our data suggest a linear dependence of the growth velocity on the Si supersaturation for  $\langle 110 \rangle$  growth, in contrast to a non-linear dependence for  $\langle 111 \rangle$  growth (Figure 1). By analyzing the surface morphologies, this difference is linked to the continuous growth mechanism on  $\{110\}$  substrate and the island nucleation controlled growth on  $\{111\}$  substrate (Figure 1). Furthermore, we find that the  $\langle 111 \rangle$  growth in our MD simulations operates in the regime where the nucleation rate is higher than the island expansion rate. This is traced to the formation of a gold saturated monolayer above the nucleated Si island, impeding its further growth. Also, it is found that the temperature dependent atom activity near the  $\{111\}$  interface is lower, explaining the smaller growth velocity of the  $\{111\}$  surface than that of the  $\{110\}$  surface.

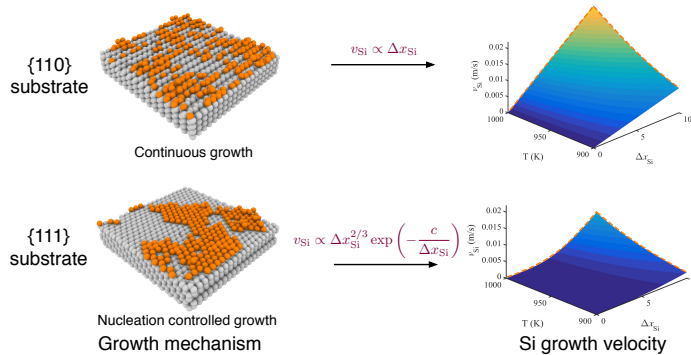


Figure 1. Growth interface morphologies (left) and growth velocities plotted as functions of temperature and Si supersaturation (right) for  $\{110\}$  and  $\{111\}$  substrates.

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[3] Y. Wang, A. Santana and W. Cai, *Journal of Applied Physics*, **122**(8), 085106 (2017).

[4] S. Ryu and W. Cai, *Journal of Physics: Condensed Matter* **22**, 055401 (2010).